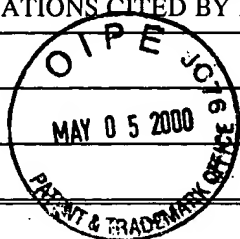


U.S. Department of Commerce, Patent and Trademark Office	Docket No.	Serial No.
(PTO Form 1449 modified)	AMAT/2966/PDD/KPU1/JW	09/165,248
LIST OF PATENTS AND PUBLICATIONS CITED BY APPLICANT	Applicant	
(Use several sheets if necessary)	Rathi et al.	
	Filing Date	Group
	October 1, 1998	2811 823



U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
G	AA	5,741,626	04/21/1998	Jain et al.	430	314	04/15/1996
G	AB	4,951,601	08/28/1990	Maydan et al.	118	719	06/23/1989
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						

Foreign Patent Documents

Translation

		Document Number	Date	Country	Class	Subclass	Yes	No
G	AK	EP0725440A2	08/07/1996	Europe	H01L	23/532	X	
	AL							
	AM							
	AN							
	AO							

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

G	AP	Ogawa et al., "Novel ARC Optimization Methodology for KrF Excimer Laser Lithography at Low K1 Factor", <i>Proceedings of the SPIE. Optical/Laser Microlithography V</i> , vol. 1674, 1992, pages 362-375.
G	AQ	Dijkstra et al., "Optimization of Anti-Reflection Layers for Deep UV Lithography", <i>Proceedings of SPIE Optical/Laser Microlithography, Bellingham, SPIE</i> , vol. 1927, pages 275-286.
G	AR	PCT International Search Report dated March 9, 2000, for PCT/US99/22424.
G	AS	PCT Partial International Search Report dated March 21, 2000, for PCT/US99/22317.

Examiner

FEARSON

Date Considered

4/21/01

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.